

(c) Amendments to the Claims

Please cancel Claims 1-18 without prejudice or disclaimer of subject matter.

Kindly add new claims 19-21. A detailed listing of all the claims that are or were in the application follows:

Claims 1-18 (Cancelled).

19. (New) A film forming method employing a reaction vessel capable of hermetic evacuation, a substrate holding member having a first end portion for holding a substrate in the reaction vessel, a source gas supply means having a second end portion for supplying a source gas, a glow discharge region and a power supply means having a third end portion for introducing a high-frequency power comprising: inducing a glow discharge by the high-frequency power to decompose the source gas introduced into the reaction vessel, thereby forming the deposited film on the substrate held by the substrate holding member, while covering the end portion of each of the substrate holding member, the source gas supply means, and the power supply means with a covering member spaced apart from each of said end portions to prevent glow discharge from occurring between each of the end portions and the covering member.

20. (New) The film forming method according to Claim 19, wherein covering the end portions is effected by an end covering member which is detachable from the reaction vessel.

21. (New) The film forming method according to Claim 19, wherein the frequency of the high-frequency power is in the range of 50 MHz to 450 MHz.